

Title (en)

PHOTORESIST REMOVER COMPOSITIONS

Title (de)

PHOTOLACKENTFERNERZUSAMMENSETZUNGEN

Title (fr)

COMPOSITIONS DE DÉCAPAGE DE RÉSINE PHOTOSENSIBLE

Publication

**EP 3997521 B1 20230830 (EN)**

Application

**EP 20740561 A 20200709**

Priority

- US 201962872950 P 20190711
- EP 2020069326 W 20200709

Abstract (en)

[origin: WO2021005140A1] The present invention relates to a composition including a sulfonic acid selected from the group consisting of an alkylbenzenesulfonic acid having structure (I), or its hydrate (wherein n is an integer from 6 to 16), a sulfosalicylic acid having structure (II), or its hydrate, and mixtures thereof and the solvent dipropylene glycol dimethyl ether [CAS registry number 111109-77-4] (III);

IPC 8 full level

**G03F 7/42** (2006.01)

CPC (source: CN EP KR US)

**B08B 3/08** (2013.01 - US); **B08B 3/10** (2013.01 - US); **G03F 7/426** (2013.01 - CN EP KR US); **B08B 2203/007** (2013.01 - US)

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